



an Open Access Journal by MDPI

Atmospheric Pressure Plasma Technologies and Applications

Guest Editors:

Dr. Evgenia Benova

Plasma Technology Laboratory, Clean&Circle Center of Competence, University of Sofia, BG-1111 Sofia, Bulgaria

Prof. Dr. Frantisek Krcma

Department of Physical and Consumer Chemistry, Faculty of Chemistry, Brno University of Technology, 61200 Brno, Czech Republic

Deadline for manuscript submissions: 15 December 2024

Message from the Guest Editors

In recent years, a large variety of plasma sources operating at atmospheric pressure have been developed. Plasma technology is gaining great attention as a "green" alternative, reducing the use of chemicals in many processes such as nanomaterials synthesis, surface treatment, disinfection, wound healing, and seeds decontamination. Since plasma is a complex system of charged particles (electrons and ions), chemically highly reactive radicals, excited atoms, and electromagnetic radiation including UV, the synergetic action of all these components makes plasma-based processes highly efficient and "clean" at the same time.

This Special Issue focuses on recent advances in atmospheric pressure plasma technologies and applications. You are invited to submit cutting-edge research, theoretical and experimental studies, as well as comprehensive reviews in this field:

- atmospheric pressure plasma
- plasma technology
- plasma applications
- cold atmospheric pressure plasma
- bio-medical plasma applications
- plasma in agriculture
- plasma technology in nanomaterials
- plasmas with liquids





mdpi.com/si/122652





an Open Access Journal by MDPI

Editor-in-Chief

Prof. Dr. Giancarlo Cravotto

Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

Message from the Editor-in-Chief

Processes (ISSN 2227-9717) provides an advanced forum for process/system-related research in chemistry, biology, material, energy, environment, food, pharmaceutical, manufacturing and allied engineering fields. The journal publishes regular research papers, communications, letters, short notes and reviews. Our aim is to encourage researchers to publish their experimental, theoretical and computational results in as much detail as necessary. There is no restriction on paper length or number of figures and tables.

Author Benefits

Open Access: free for readers, with article processing charges (APC) paid by authors or their institutions. **High Visibility:** indexed within Scopus, SCIE (Web of Science), Ei Compendex, Inspec, AGRIS, and other databases. **Journal Rank:** JCR - Q2 (*Engineering, Chemical*) / CiteScore - Q2 (*Chemical Engineering* (miscellaneous))

Contact Us

Processes Editorial Office MDPI, St. Alban-Anlage 66 4052 Basel, Switzerland Tel: +41 61 683 77 34 www.mdpi.com mdpi.com/journal/processes processes@mdpi.com X@Processes_MDPI